U.S. Patent Application No.: 10/538,690 Filing Date: 10 June 2005 First Named Inventor: Yamada et al.

## Current version of the Claims

This is a complete listing of claims and supersedes all other listings:

 (previously presented) A saponified poly(vinyl acetate)-based photosensitive resin characterized by having a structural unit represented by formula (1):

(wherein  $R_1$  represents H or Me;  $R_2$  represents a linear or branched C2-C10 alkylene group; n is an integer of 1 to 3; X represents

m is an integer of 0 to 6; and Y represents an aromatic ring or a single bond).

- (original) A photosensitive resin composition comprising a photosensitive resin according to claim 1.
- (original) A photosensitive resin composition according to claim 2, which further comprises a least one photopolymerization initiator.
- (previously presented) A photosensitive resin composition according to claim 2, which further comprises water.
- (previously presented) A method for forming a hydrogel comprising subjecting a
  photosensitive resin composition as recited in claim 2 to photopolymerization.
  - 6. (previously presented) A compound represented by formula (2):

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(wherein R<sub>1</sub> represents H or Me; R<sub>2</sub> represents a linear or branched C2-C10 alkylene group; X represents

 $\boldsymbol{m}$  is an integer of 0 to 6; and Y represents an aromatic ring or a single bond).

7. (previously presented) A compound represented by formula (3):

(wherein R<sub>1</sub> represents H or Me; R<sub>2</sub> represents a linear or branched C2-C10 alkylene group; X represents

$$\begin{array}{c} \begin{array}{c} H_2 \\ C \end{array} \end{array}, \begin{array}{c} C \\ C \end{array} \end{array}$$

m is an integer of 0 to 6; Y represents an aromatic ring or a single bond; and each of R<sub>3</sub> and R<sub>4</sub> represents a C1-C3 alkyl group).

- (previously presented) A photosensitive resin composition according to claim 3, which further comprises water.
- (previously presented) A method for forming a hydrogel comprising subjecting a
  photosensitive resin composition as recited in claim 3 to photopolymerization.

 (previously presented) A method for forming a hydrogel comprising subjecting a photosensitive resin.